

First Named Inventor : Kalman Pelhos  
Appln. No. : 10/673,795  
Filed : September 29, 2003  
Title : SYSTEM, METHOD AND APERTURE FOR OBLIQUE DEPOSITION  
Docket No. : I69.12-0582

Group Art Unit: 1762

Examiner:

### SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner For Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I CERTIFY THAT THIS PAPER IS BEING SENT BY U.S. MAIL, FIRST CLASS, TO THE ASSISTANT COMMISSIONER FOR PATENTS, ALEXANDRIA, VA 22313, THIS 1<sup>st</sup> DAY OF

April, 2004.

PATENT ATTORNEY

Sir:

The enclosed PTO Form-1449 lists patents and publications submitted pursuant to 37 C.F.R. 1.97. Copies of the patents or publications are enclosed as necessary.

Submitted herewith is a copy (with English translation as appropriate) of an Official Search Report of the Patent Cooperation Treaty Patent Office in counterpart foreign Application No. PCT/US 03/30507 filed September 29, 2003.

#### TIME OF FILING

The Information Disclosure Statement is being filed:

1. X with the application or within three months of the filing date of a national application (other than a continued prosecution application under 37 C.F.R. 1.53(d)) or date of entry into the national stage of an international application or, to the best of the undersigned's knowledge, before the mailing date of a first Office action on the merits or a first office action after the filing of a request for continued examination under 37 C.F.R. 1.114, whichever event occurs last. In accordance with 37 C.F.R. 1.97(b), no certification or fee is required.

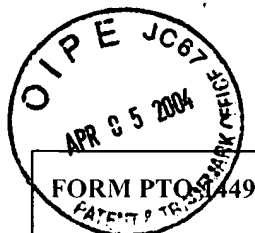
Respectfully submitted,

KINNEY & LANGE, P.A.

By:   
Ann Kulprathpanja, Reg. No. 50,608

THE KINNEY & LANGE BUILDING  
312 South Third Street  
Minneapolis, MN 55415-1002  
Telephone: (612) 339-1863  
Fax: (612) 339-6580

AK:sas



LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: I69.12-0556	Application No.: 10/674,173
	First Named Inventor: Kalman Pelhos	
	Filing Date: September 29, 2003	Group Art: 2652

## U.S. PATENT DOCUMENTS

Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA			
AB			

## FOREIGN PATENT DOCUMENTS

	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
AC	WO8007250	06-14-1994	Hitachi Ltd	No
AD	2002042326	07-19-2000	KYOCERA CORP	Yes

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AE	Kiwamu Tanahashi, Yuzuru Hosoe, Masaaki Futamoto; <i>Magnetic Anisotropy and Microstructure of Obliquely Evaporated Co/Cr Thin Films</i> ; July 24, 1995; pgs. 265 - 272.
AF	Y.F. Zheng and J.P. Wang; <i>Control of the Tilted Orientation of CoCrPt/Ti thin film media by collimated sputtering</i> ; May 15, 2002; V931 pgs. 0007 - 0009.
AG	M.J. Hadley, R. Atkinson, R.J. Pollard; <i>Magnetic Properties of Co Films Deposited Onto Obliquely Sputtered Ta Underlayers</i> ; January 31, 2002.
AH	Dieter Weller and Andreas Moser; <i>Thermal Effect Limits in Ultrahigh-Density Magnetic Recording</i> ; November 1999; volume 35, pgs. 4423 - 4439.
AI	R.D. McMichael, C.G. Lee, J.E. Bonevich, P.J. Chen, W. Miller, and W.F. Egelhoff, Jr; <i>Strong Anisotropy in Thin Magnetic Films Deposited on Obliquely Sputtered Ta Underlayers</i> ; volume 88, No. 9, pgs. 5296 - 5299.0
AJ	A. Hagemeyer, H.J. Richter, H. Hibst, V. Maier and L. Marosi; <i>Crystallographic Texture and Morphology of Obliquely Deposited Co-Cr Magnetic Thin Films on Flexible Polymeric Substrates</i> ; August, 10, 1993; pgs. 199 - 202.
AK	T. Hikosaka, Y. Tamaka, T. Sonoda, and R. Nishikawa; <i>Cr Underlayer's Effect on the Magnetic and Crystalline Properties of Co Alloy Film</i> ; June 1988; volume 3, No. 6, pgs. 423 - 424.
AL	J.C. Lodder; <i>Magnetic Thin Films for High-Density Recording</i> ; 1996; pgs 474 -483

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.